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| Substitute for form 1449/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary) | | | | Complete if Known | |
| | | | | Application Number | 10/596,626-Conf. #8534 |
| | | | | Filing Date | June 19, 2006 |
| | | | | First Named Inventor | Karl-Heinz Schuster |
| | | | | Art Unit | N/A |
| | | | | Examiner Name | Not Yet Assigned |
| Sheet | 1 | of | 1 | Attorney Docket Number | 01641/0204258-US0 |

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| NON PATENT LITERATURE DOCUMENTS | | | | |
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| Examiner Initials | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | | T ² |
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| Examiner Signature | /Evelyn Lester/ | Date Considered | 11/07/2008 |
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